

PATENT APPLICATION

Serial No: 10/_____
Filing Date: December 12, 2003
First Named Inventor: Steven A. Soper
Title: Photoresist-Free Micropatterning on Polymer Surfaces
Atty Docket: 0023.1 Soper

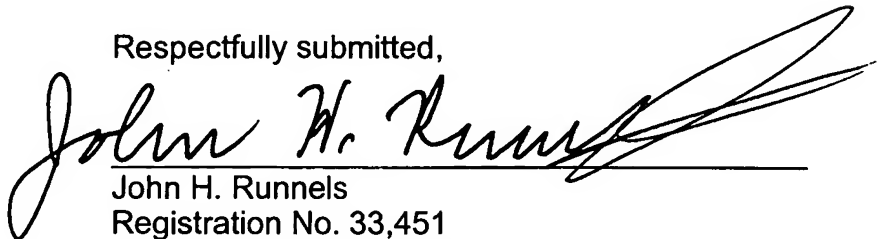
MS PATENT APPLICATION
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

In accordance with the duty of candor and good faith imposed by 37 C.F.R. §1.56 and means of complying therewith according to 37 C.F.R. §§1.97 and 1.98, the references listed on the attached Information Disclosure Citation are called to the attention of the United States Patent and Trademark Office in connection with the above-identified patent application. A copy of the cited references are enclosed herewith. No admission is made that the cited art represents the prior art or that the cited art is the most material art.

The Office is urged to consider the cited references and to make an independent decision with respect to their materiality.

Respectfully submitted,



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Substitute for form 1449A/PTO		U.S. Patent and Trademark Office U.S. Department of Commerce		COMPLETE IF KNOWN	
INFORMATION DISCLOSURE CITATION (use as many sheets as necessary)				Application Number	10/_____
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				First Named Inventor	Steven A. Soper
				Art Unit	
				Examiner Name	
Sheet	1	of	2	Attorney Docket No.	0023.1 Soper

U.S. PATENT DOCUMENTS						
Exam. Initial	Document No.	Date	Name	Class	Subcl.	File Date
	6,436,615	8/02	Brandow <i>et al.</i>	430	324	6/25/99
	5,051,312	9/91	Allmer	428	458	

Note: Copies of U.S. Patents are not enclosed. See OG Notice of August 5, 2003.

FOREIGN PATENT DOCUMENTS				
Exam. Initial	Foreign Patent Document	Publication Date MM-DD-YY	Name of Patentee or Applicant of Cited Document	Translation ?
	Country Code / Number / Kind			
	WO 02/18288	03-07-02	Hevesi <i>et al.</i>	
	WO 00/56808	09-28-00	Larsson <i>et al.</i>	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)	
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EXAMINER SIGNATURE	DATE CONSIDERED
<p>* EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw a line through the citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>	

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